

EV 26161597

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. .... 09/026,042  
Priority Filing Date ..... February 19, 1998  
Inventor ..... Sujit Sharan et al.  
Assignee ..... Micron Technology, Inc. and Applied Materials, Inc.  
Priority Group Art Unit ..... 1763  
Priority Examiner ..... P. Hassanzadeh, Ph.D.  
Attorney's Docket No. .... MI22-1902  
TITLE: RF Powered Plasma Enhanced Chemical Vapor Deposition Reactor and  
Methods of Effecting Plasma Enhanced Chemical Vapor Deposition

Assistant Commissioner for Patents  
Washington, D. C. 20231  
Attention: Official Draftsman


**SUBSTITUTE DRAWING REQUEST**

Please enter the enclosed substitute drawings in the above-referenced application in place of drawings originally filed. The content of the drawings are identical to those now on file in this application.

Acknowledgment of receipt of the formal drawings and their acceptance into the file is requested.

Respectfully submitted,

Date: Feb 19, 2002

By:   
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Enclosures: 4 Sheets of Formal Drawings, Figs. 1-6.

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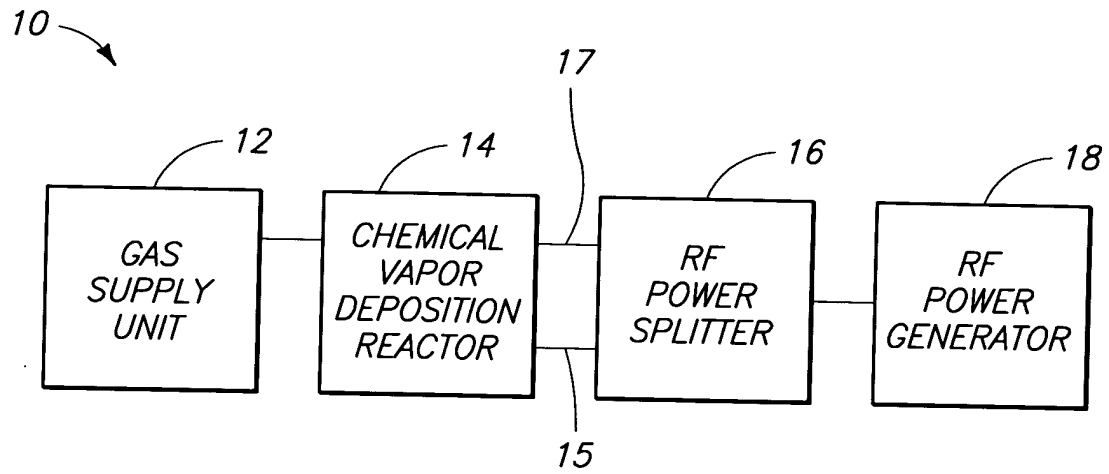


FIG. 1

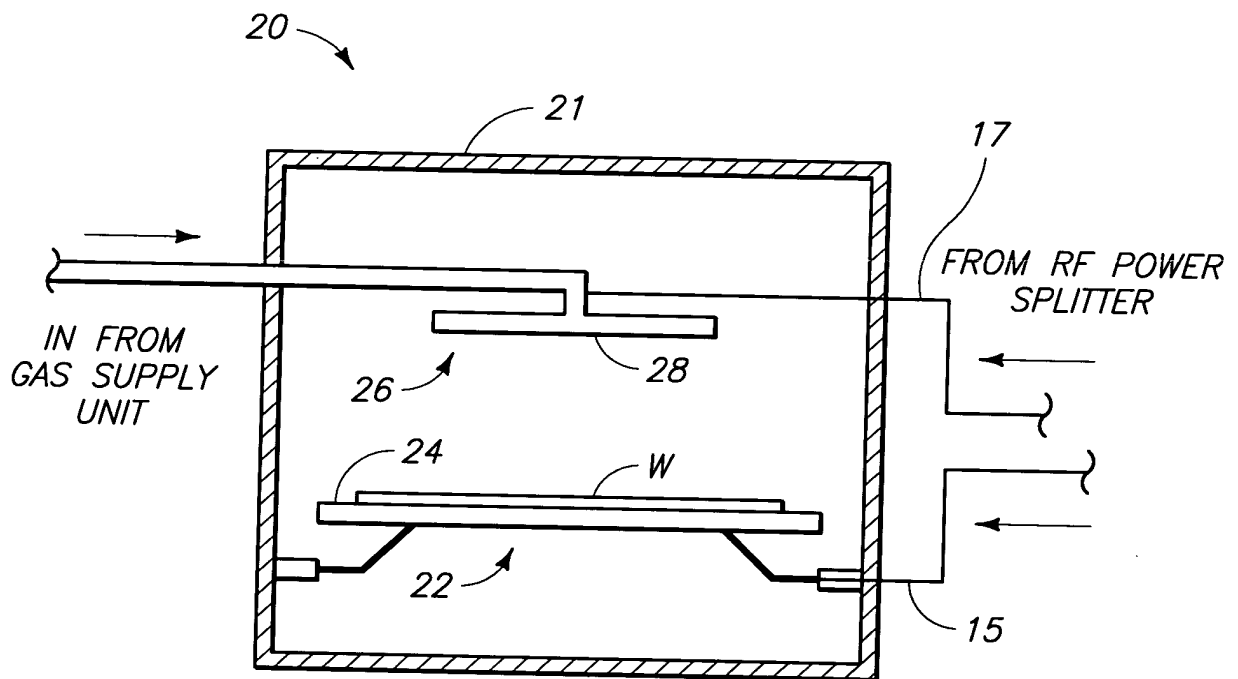
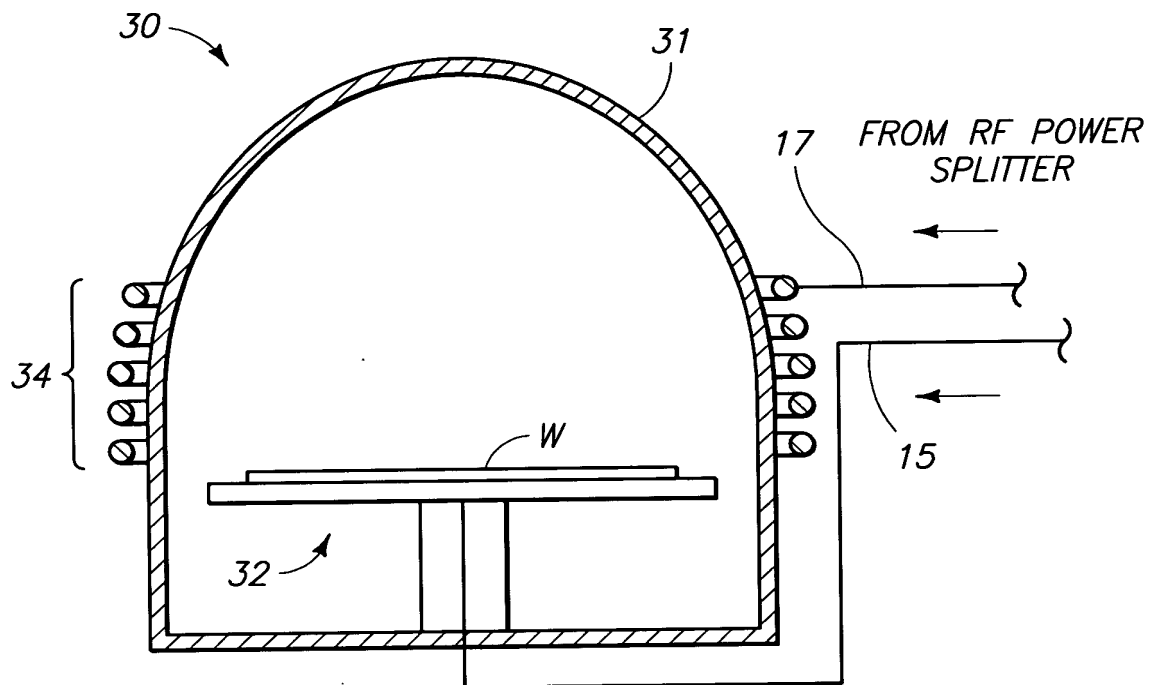
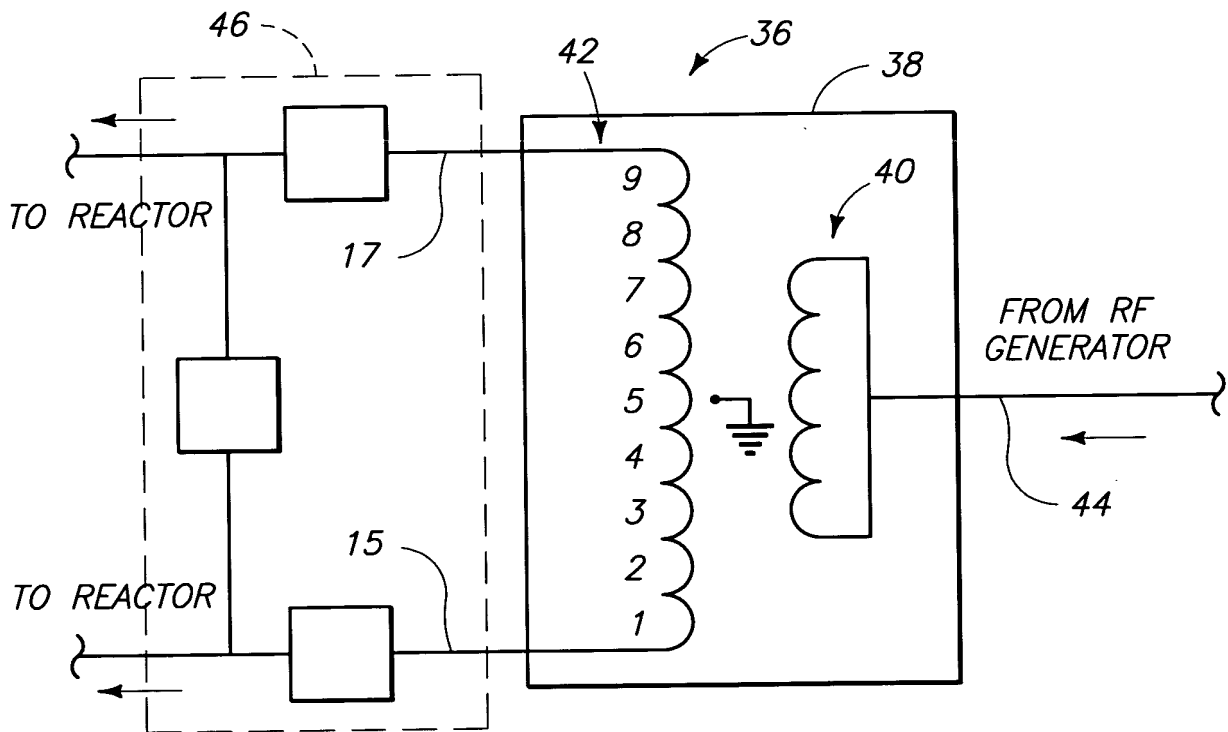


FIG. 2

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*FIG. 2*



*FIG. 3*

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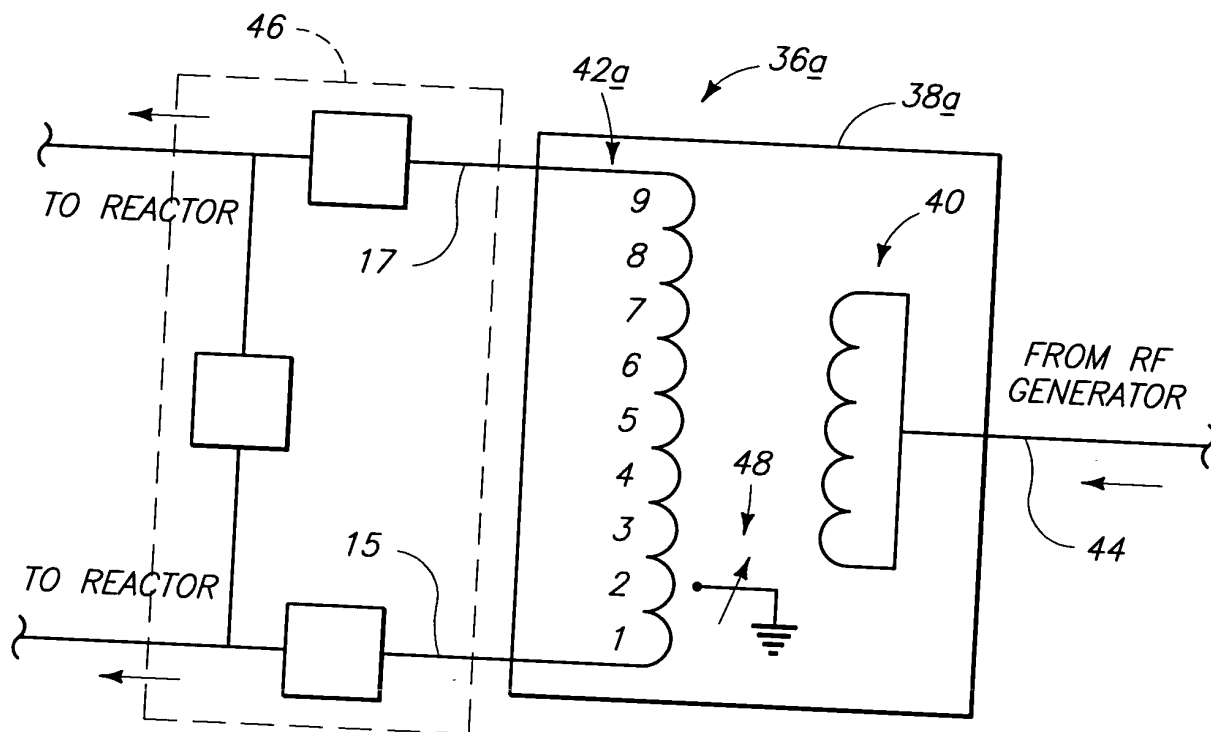


FIG. 5

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